IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:)
Song et al.) Group Art Unit: 1752
Serial No.:10/720,966) Examiner: John S. Y. Chu
Filed: November 24, 2003) Confirmation No.: 5221
For: PHOTORESIST COMPOSITION AND METHOD PATTERN FORMING USING THE SAME) TKHR Docket: 250913-1030) Top-Team: 0424-8857US

RESPONSE TO FINAL OFFICE ACTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

The FINAL Office Action mailed November 14, 2006, has been carefully considered. In response thereto, Applicants hereby submit following remarks and the accompanying petition for a 2-month extension of time. Reconsideration and allowance of the application and presently pending claims, as amended, are respectfully requested.